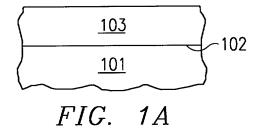
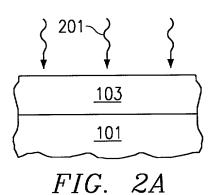
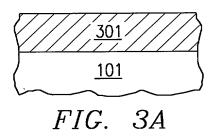
1/5



STEP 1: GATE OXIDATION 0.8-2.0 nm ~ 104



STEP 2: PLASMA NITRIDATION 100-500W, 20-80 mTorr, He/N $_2$ =75/25%, 10-60s



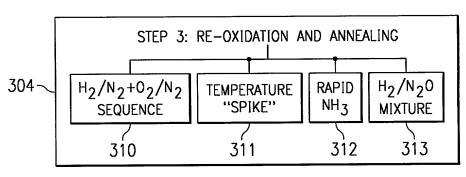
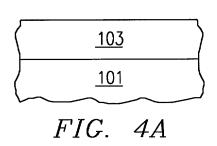
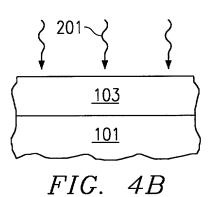
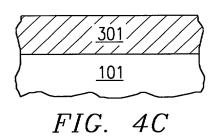
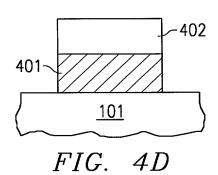


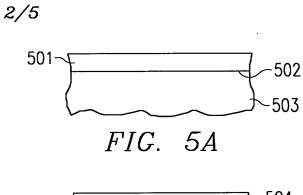
FIG. 3B

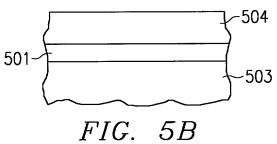


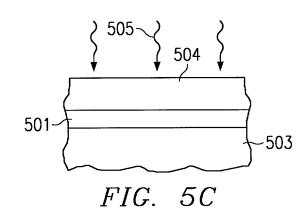


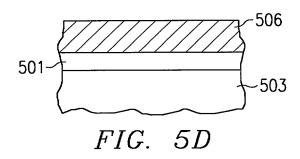


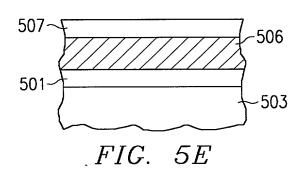


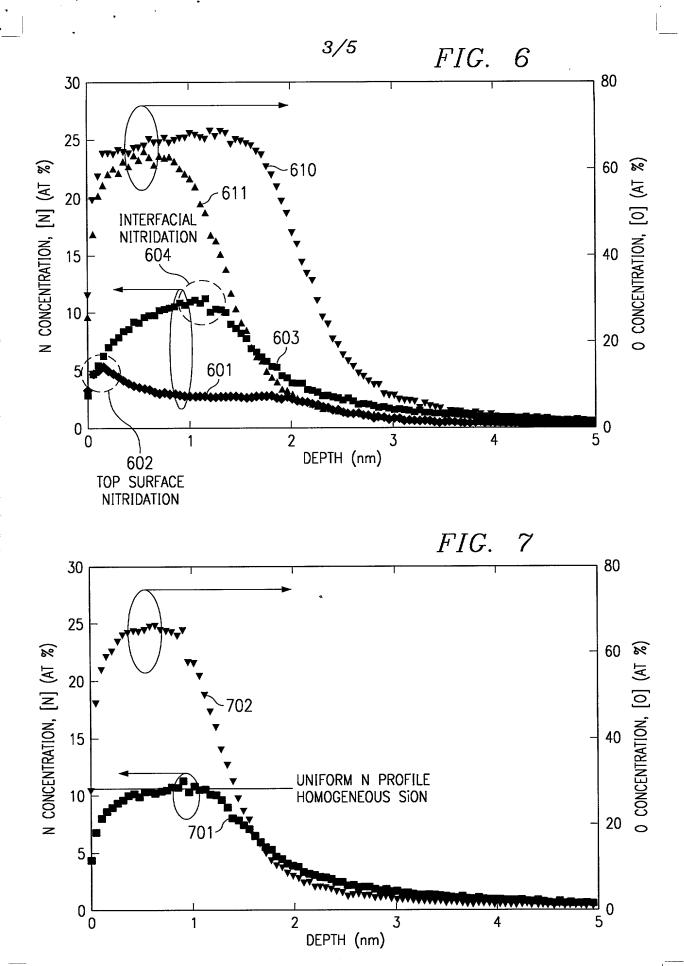












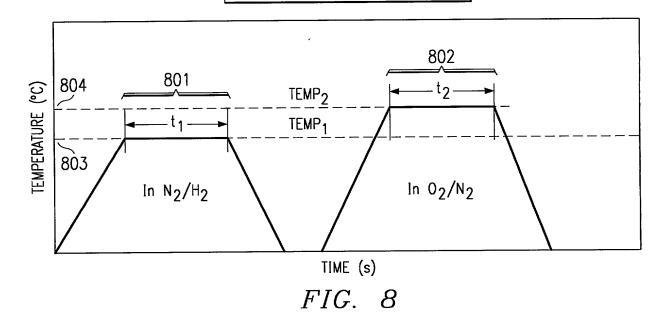
4/5

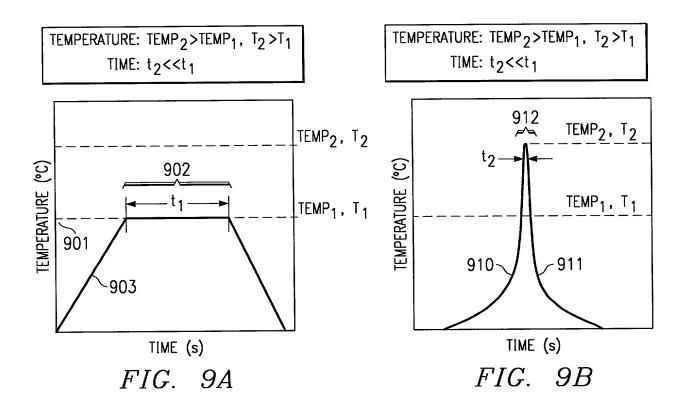
TEMPERATURE: TEMP₁=600-1000°C

 $TEMP_2 = 800 - 1000^{\circ}C$

TIME: $t_1 = 5 - 60s$

 $t_2 = 5 - 60s$

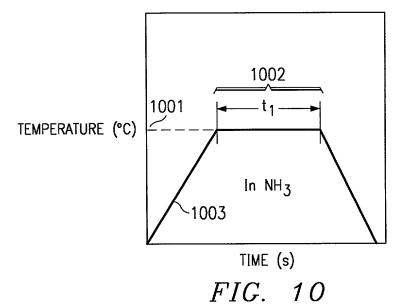




5/5

TEMPERATURE: T₁=TEMP₁=600-1000°C

TIME: $t_1 = 5 - 60s$



TEMPERATURE: T₁=TEMP₁=800-1050°C

TIME: $t_1 = 5 - 60s$

